



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Fabio Pellizzer
Application No. : 10/824,631
Filed : April 14, 2004
For : SELF-ALIGNED PROCESS FOR MANUFACTURING
A PHASE CHANGE MEMORY CELL AND PHASE
CHANGE MEMORY CELL THEREBY
MANUFACTURED

Examiner : Joseph H. Nguyen
Art Unit : 2815
Docket No. : 854163.414
Date : June 19, 2006

Mail Stop RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT TRANSMITTAL

Commissioner for Patents:

In accordance with 37 CFR 1.56 and 1.97 through 1.98, applicant wishes to make known to the U.S. Patent and Trademark Office the references set forth on the attached Information Disclosure Statement. Copies of cited U.S. patents and published patent applications are not required and accordingly have not been provided. Copies of any other cited references are enclosed. Applicants wish to disclose and have officially considered the following co-pending related applications by the same assignee: Application No. 10/313,991, filed December 5, 2002, entitled SMALL AREA CONTACT REGION, HIGH EFFICIENCY PHASE CHANGE MEMORY CELL AND FABRICATION METHOD THEREOF; Application No. 10/756,195, filed January 13, 2004, entitled "SUBLITHOGRAPHIC CONTACT STRUCTURE, IN PARTICULAR FOR A PHASE CHANGE MEMORY CELL, AND FABRICATION PROCESS THEREOF", Application No. 11/045,170, filed January 27, 2005, entitled "PHASE


CHANGE MEMORY CELL AND MANUFACTURING METHOD THEREOF USING MINITRENCHES”; Application No. 11/156,989, filed June 20, 2005, entitled “CONTACT STRUCTURE, PHASE CHANGE MEMORY CELL, AND MANUFACTURING METHOD THEREOF WITH ELIMINATION OF DOUBLE CONTACTS”; Application No. 11/258,340 filed October 24, 2005, entitled “SUBLITHOGRAPHIC CONTACT STRUCTURE, PHASE CHANGE MEMORY CELL WITH OPTIMIZED HEATER SHAPE, AND MANUFACTURING METHOD THEREOF”. As to any reference cited, applicant does not admit that it is “prior art” under 35 U.S.C. §§ 102 or 103, and specifically reserves the right to traverse or antedate any such reference, as by a showing under 37 CFR 1.131 or other method. Although the aforesaid references are made known to the Patent and Trademark Office in compliance with applicant’s duty to disclose all information he is aware of which is believed relevant to the examination of the above-identified application, applicant believes that his invention is patentable.

Please acknowledge receipt of this Supplemental Information Disclosure Statement and kindly make the cited references of record in the above-identified application.

The Director is authorized to charge any other fees which may be required, or credit any overpayment to Deposit Account No. 19-1090.

Respectfully submitted,

Seed Intellectual Property Law Group PLLC



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HXH:lcs

Enclosures:

Supplemental Information Disclosure Statement
Cited References (2)

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U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE**SUPPLEMENTAL
INFORMATION DISCLOSURE STATEMENT**
(Use several sheets if necessary)ATTY. DOCKET NO.
854163.414APPLICATION NO.
10/824,631APPLICANT
Fabio PellizzerFILING DATE
April 14, 2004GROUP ART UNIT
2815**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	5,789,277	08/04/98	Zahorik et al.	438	95	
	AB	5,814,527	09/29/98	Wolstenholme et al.	438	5	
	AC	5,952,671	09/14/99	Reinberg et al.	257	3	
	AD	5,970,336	10/19/99	Wolstenholme et al.	438	238	
	AE	6,031,287	02/29/00	Harshfield	257	734	
	AF	6,238,946	05/29/01	Ziegler	438	50	
	AG	6,313,604	11/06/01	Maimon et al.	438	95	
	AH	6,541,333	04/01/03	Shukuri et al.	438	243	
	AI	6,613,604	09/02/03	Maimon et al.	438	95	
	AJ	6,617,192	09/09/03	Lowrey et al.	438	95	
	AK	6,750,079	06/15/04	Lowrey et al.	438	95	
	AL	6,759,267	07/06/04	Chen	438	95	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AM	WO 00/57498	09/28/00	WIPO		
	AN					
	AO					
	AP					

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AQ	Palun, L. et al., "Fabrication of Single Electron Devices by Hybrid (E-Beam/DUV) Lithography," Microelectronic Engineering 53, pp. 167-170, 2000.
	AR	

EXAMINER

DATE CONSIDERED

* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)	ATTY. DOCKET NO. 854163.414	APPLICATION NO. 10/824,631
	APPLICANT Fabio Pellizzer	
	FILING DATE April 14, 2004	GROUP ART UNIT 2815

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	BA	6,777,705	08/17/04	Reinberg et al.	257	2	
	BB	6,943,365	09/13/05	Lowrey et al.	257	3	
	BC	6,972,430	12/06/05	Casagnade et al.	257	4	
	BD	6,969,866	11/29/05	Lowrey et al.	257	3	
	BE	2002/0070401	06/13/02	Takeuchi et al.	257	296	
	BF	2003/0075778	04/24/03	Klersy	257	536	
	BG	2003/0219924	11/27/03	Bez et al.	438	102	
	BH	2004/0113181	01/22/04	Klebanoff et al.	134	2	
	BI	2004/0166604	08/26/04	Ha et al.	438	102	
	BJ	2004/0245603	12/09/04	Lowrey et al.	257	536	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	BK					
	BL					
	BM					
	BN					
	BO					

OTHER PRIOR ART *(Including Author, Title, Date, Pertinent Pages, Etc.)*

	BP		
	BQ		
	BR		

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